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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/560,268	04/26/2000	Whonchee Lee	150.0056 0102	2517
75	90 02/14/2003			
Attn Mark J Gebhardt			EXAMINER	
Mueting Raasch Gebhardt PA PO Box 581415			DEO, DUY VU NGUYEN	
Minneapolis, M	N 55458-1415		ART UNIT	PAPER NUMBER
			1765	01
			DATE MAILED: 02/14/2003	21

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	plicant(s)	
Advisory Action	09/560,268	LEE ET AL.	
Advisory Action	Examiner	Art Unit	
	DuyVu n Deo	1765	
The MAILING DATE of this communication a	ppears on the cover sheet w	vith the correspondence address	
THE REPLY FILED 04 February 2003 FAILS TO PLA Therefore, further action by the applicant is required to inal rejection under 37 CFR 1.113 may <u>only</u> be either: condition for allowance; (2) a timely filed Notice of App Examination (RCE) in compliance with 37 CFR 1.114.	: (1) a timely filed amendm peal (with appeal fee); or (3	ent which places the application in b) a timely filed Request for Contin	1
	REPLY [check either a) or	(b)]	
a) The period for reply expires 3 months from the mailing b) The period for reply expires on: (1) the mailing date of t no event, however, will the statutory period for reply exp ONLY CHECK THIS BOX WHEN THE FIRST REPLY V 706.07(f).  Extensions of time may be obtained under 37 CFR 1.136(a). The have been filed is the date for purposes of determining the period and the second se	this Advisory Action, or (2) the date pire later than SIX MONTHS from WAS FILED WITHIN TWO MON The date on which the petition united of extension and the correspondent of the shortened statutory period. Office later than three months at	THE OF THE FINAL REJECTION. See Monder 37 CFR 1.136(a) and the appropriate and ing amount of the fee. The appropriate of the fee the appropriate of the a	extension extension action; or
1. A Notice of Appeal was filed on Appella 37 CFR 1.192(a), or any extension thereof (37	ant's Brief must be filed witl CFR 1.191(d)), to avoid dis	nin the period set forth in smissal of the appeal.	
2. The proposed amendment(s) will not be entere	ed because:		
(a)  they raise new issues that would require fu	urther consideration and/or	search (see NOTE below);	
(b) ☐ they raise the issue of new matter (see No	ote below);		
(c) they are not deemed to place the application issues for appeal; and/or			ing the
(d)  they present additional claims without car	nceling a corresponding nu	mber of finally rejected claims.	
NOTE:			
3. Applicant's reply has overcome the following re	ejection(s):		
canceling the non-allowable claim(s).		ed in a separate, timely filed amer	
5. ☑ The a) ☐ affidavit, b) ☐ exhibit, or c) ☑ reques application in condition for allowance because	t for reconsideration has bear See Continuation Sheet.	en considered but does NOT plac	ce the
6. The affidavit or exhibit will NOT be considered raised by the Examiner in the final rejection.			
7. For purposes of Appeal, the proposed amendate explanation of how the new or amended claim	ment(s) a) will not be ent ns would be rejected is prov	ered or b)  will be entered and a vided below or appended.	n
The status of the claim(s) is (or will be) as follo	ows:		
Claim(s) allowed:			
Claim(s) objected to:			
Claim(s) rejected: <u>64, 65, 67-95</u> .			
Claim(s) withdrawn from consideration:			
8. The proposed drawing correction filed on	_ is a)□ approved or b)[	disapproved by the Examiner.	
9. Note the attached Information Disclosure State			
10. Other:			

Continuation of 5. does NOT place the application in condition for allowance because: applicant has not provide evidence that solution of Shiramizu or Nakano does not have the same etching rate as that of the claimed invention. the chemical concentrations and their ratio in the solution are probably the most important factors in determining the etching rate. since solution described by Shiramizu and Nakano has substantially the same chemical concentrations and ratio, their solution would have the same etching rate as that of the claimed invention.

BENJAMIN L. UTECH SUPERVISORY PATENT EXAMINER

TECHNOLOGY CENTER 1700

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